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OFFICIAL

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

KABASAWA

Art Unit: 2881

Application Number: 09/629,618

Examiner: B. Souw

Filed: July 31, 2000

Atty. Docket No.: 107443-00007

For: ION IMPLANTATION APPARATUS AND ION IMPLANTATION METHOD

RESPONSE TO QUAYLE ACTION

Commissioner for Patents
Washington, D.C. 20231

June 30, 2003

Sir:

This paper is filed in response to the Office Action dated May 7, 2003, in connection with the above-identified patent application. Applicant respectfully requests entry of the following amendments.

IN THE SPECIFICATION:

Please amend the specification as follows:

Page 2, paragraph [0005], please amend as follows:

[0005] According to inventors' experimental studies, it has been found out that ions with undesirable energy are implanted into the wafer and give rise to serious energy contamination, when the ions are implanted into the wafer with very low energy with the

TECH/183584.1